

II. Statement of Substance of Interview

Applicants gratefully acknowledge a personal interview with Examiner Eslami and Supervisory Patent Examiner (SPE) Cleveland, conducted October 5, 2011.

During the interview, the differences between the claims and the cited references were discussed. The Examiners stated that the arguments are convincing and that the current claims rejections would be withdrawn upon filing of a formal Response.

III. Preliminary Matters

Applicants thank the Examiner for acknowledging the claim for foreign priority and receipt of the certified copies of the foreign priority documents.

Applicants also thank the Examiner for accepting the drawings filed May 30, 2006.

V. Claim Rejections - 35 U.S.C. § 102

Claims 1-6, 10, 20-22, 26-28, and 30 are rejected under 35 U.S.C. 102(b) as being anticipated by Touto.

Claim 1 recites “forming on a substrate a polymer layer in a pattern form by using a compound which has a polymerizable group and a functional group that interacts with an electroless plating catalyst or a precursor thereof.”

That is, according to independent claim 1, a specific compound has both “a polymerizable group” and “a functional group that interacts with an electroless plating catalyst or a precursor thereof” in one molecule. This compound has both the polymerizable capability and interactional capability with a catalyst and is able to generate a polymer included in the polymer layer.

Touto does not disclose or suggest a specific compound which has both a "polymerizable group" and a "specific functional group" in one molecule, or a process for generating a polymer by using a compound such as the claimed specific compound.

Further, in the Office Action, Examiner asserts that the photosensitive resin disclosed in Touto inherently has a functional group (i.e., that a polymer of polyether sulphone and diaryl terelathalate would have ether, thio and aryl functional groups).